	Application No.	Applicant(s)
Notice of Allowability		
	10/695,479 Examiner	MASCOLO ET AL. Art Unit
	David Nhu	2818
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to 3/2/05.		
2. The allowed claim(s) is/are 1-17 and 24-41.		
3. The drawings filed on 28 October 2003 are accepted by the Examiner.		
 4.		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	6. Intérview Summary Paper No./Mail Dat 7. Examiner's Amendr 8. Examiner's Stateme 9. Other	te

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REASONS FOR ALLOWANCE

1. Claims 1-17, 24-41 are allowed.

2. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests in claims 1, 11, 37: providing passivated metallic nanoclusters; electro-migrating the passivated metallic nanoclusters by forcing the passivated metallic nanoclusters to assemble over the patterned substrate under control of a non-homogeneous electric field (se cited in claim 1); forming conductive naoparticles; forming a nanocluster contact at a first electrode by forcing the conductive nanoparticles to the first electrode under control of a non-homogeneous electric field produced by a second electrode (as cited in claim 11); patterning a substrate to provide an integrated microcavity, said integrated microcavity being substantially rectangular and surrounded on four sides by metal contacts, and forming a naowire within the integrated microcavity (as cited in claim 37).

3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

CONCLUSION

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Winningham et al (6,579,463): Tunable Nanomasks for Pattern Transfer and Nanocluster array Formation.

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Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (571)272-1792. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (571)272-1787.

The fax phone number for the organization where this application or proceeding is assigned is (571)273-1792.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

David Nhu

March 23, 2005

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